

IEUVI Resist TWG Meeting Agenda

Nov. 1, 2007

Sapporo Convention Center, Room 107/108

12:00	Lunch	All
13:00	Welcome, Introductions	<u>Kim Dean</u> (SEMATECH)
13:15	Regional Updates including Exposure Tool Presentations	Mieke Goethals (IMEC), <u>Serge Tedesco</u> (CEA/LETI), <u>Toshiro Itani</u> , (Selete), <u>K. Dean</u> (SEMATECH), <u>David Stark</u> (SEMATECH), <u>John Hartley</u> (U. Albany), Solak Harun (PSI)
14:45	Tool Dose Calibration	<u>Robert Brainard</u> (U. Albany)
15:15	Break	
15:30	Dynamics of Chemical Intermediates in CARs of Post-optical Lithographies	Akinori Saeki (Osaka University)
16:00	Required Resist Performance for 32, 22 and 16nm hp based on a single Figure of Merit	<u>Koen Van Ingen Schenau</u> (ASML)
16:20	Wrap up, Topics for Next Meeting	<u>S. Tedesco</u> (CEA/LETI)
16:30	Adjourn	